

**Amendments to the Claims:**

This listing of claims will replace all prior versions, and listings, of claims in the application:

**Listing of Claims:**

1. (Currently Amended) A method of producing a superconductor, comprising the step of forming a superconducting layer on a base layer by performing a film deposition at least three times without substantially changing an oxygen gas pressure between the at least three times, wherein the a film thickness of a superconducting film made in each film deposition is 0.3  $\mu\text{m}$  or less and the superconducting layer having a layer thickness of 0.75  $\mu\text{m}$  to 3  $\mu\text{m}$  is formed on the base layer and wherein the base layer is composed of Ni, Cr, Mn, Co, Fe, Pd, Cu, Ag or Au or an alloy of at least two of Ni, Cr, Mn, Co, Fe, Pd, Cu, Ag or Au.
2. (Cancelled)
3. (Currently Amended) AThe method of producing a superconductor according to claim 1, wherein a supply area velocity of the base layer in each film deposition is at least 0.04  $\text{m}^2/\text{h}$ .
4. (Currently Amended) A superconductor comprising a superconducting layer formed by performing film deposition on a base layer at least three times without substantially changing an oxygen gas pressure between the at least three times, wherein the superconducting layer has a layer thickness in the a range of 0.75  $\mu\text{m}$  to 3.0  $\mu\text{m}$ , the a film thickness of a superconducting film made in each film deposition being 0.3  $\mu\text{m}$  or less and wherein the base layer is composed of Ni, Cr, Mn, Co, Fe, Pd, Cu, Ag or Au or an alloy of at least two of Ni, Cr, Mn, Co, Fe, Pd, Cu, Ag or Au.
5. (New) The method according to claim 1, wherein the oxygen gas pressure is maintained at approximately 200 mTorr during the at least three times of the film deposition and between the at least three times.

6. (New) The method according to claim 1, wherein the film deposition is stopped between each of the at least three times of performing the film deposition.
7. (New) The superconductor according to claim 4, wherein a supply area velocity of the base layer in each film deposition is at least  $0.04\text{m}^2/\text{h}$ .
8. (New) The superconductor according to claim 4, wherein the oxygen gas pressure is maintained at approximately 200 mTorr during the at least three times of the film deposition and between the at least three times.
9. (New) The superconductor according to claim 4, wherein the film deposition is stopped between each of the at least three times of performing the film deposition.